

# Martijn F J Vos

## List of Publications by Year in Descending Order

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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

9

papers

176

citations

5

h-index

9

g-index

9

ext. papers

224

ext. citations

4

avg, IF

3.06

L-index

#	Paper	IF	Citations
9	Atomic layer deposition and selective etching of ruthenium for area-selective deposition: Temperature dependence and supercycle design. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2021</b> , 39, 032412	2.9	2
8	Reaction Mechanisms during Atomic Layer Deposition of AlF Using Al(CH) and SF Plasma. <i>Journal of Physical Chemistry C</i> , <b>2021</b> , 125, 3913-3923	3.8	3
7	Atomic layer deposition of ruthenium using an ABC-type process: Role of oxygen exposure during nucleation. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2020</b> , 38, 062402	2.9	6
6	Plasma-Enhanced Atomic Layer Deposition of Cobalt and Cobalt Nitride: What Controls the Incorporation of Nitrogen?. <i>Journal of Physical Chemistry C</i> , <b>2020</b> , 124, 22046-22054	3.8	3
5	Isotropic plasma atomic layer etching of Al <sub>2</sub> O <sub>3</sub> using a fluorine containing plasma and Al(CH <sub>3</sub> ) <sub>3</sub> . <i>Applied Physics Letters</i> , <b>2020</b> , 117, 162107	3.4	5
4	Area-Selective Deposition of Ruthenium by Combining Atomic Layer Deposition and Selective Etching. <i>Chemistry of Materials</i> , <b>2019</b> , 31, 3878-3882	9.6	46
3	Atomic Layer Deposition of Cobalt Using H-, N-, and NH-Based Plasmas: On the Role of the Co-reactant. <i>Journal of Physical Chemistry C</i> , <b>2018</b> , 122, 22519-22529	3.8	23
2	Atomic layer deposition of molybdenum oxide from (NtBu) <sub>2</sub> (NMe <sub>2</sub> ) <sub>2</sub> Mo and O <sub>2</sub> plasma. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , <b>2016</b> , 34, 01A103	2.9	78
1	Concepts and prospects of passivating contacts for crystalline silicon solar cells <b>2015</b> ,		10